

**IN THE CLAIMS**

Please cancel claims 8-12, without prejudice or disclaimer.

1. (Original) An electron beam exposure mask comprising:

a main mask having a plurality of first defined masks; and

one or more compensation masks including one or more non-defective second defined masks each having a pattern configuration to be formed in a defective among said first defined masks.

2. (Original) The electron beam exposure mask according to claim 1, wherein said main mask and at least one compensation mask are arranged on the same substrate.

3. (Original) The electron beam exposure mask according to claim 1, wherein said compensation mask includes one or more non-defective third defined masks each having a pattern configuration to be formed in part of said first defined masks irrespective of the presence or absence of a defective among said first defined masks.

4. (Original) The electron beam exposure mask according to claim 3, wherein said compensation mask includes a plurality of identically patterned defined masks.

5. (Original) The electron beam exposure mask according to claim 3, wherein said second defined masks are arranged adjacent to said main mask.

6. The electron beam exposure mask according to claim 3, wherein said second defined masks are arranged in the periphery of said main mask.

7. (Original) The electron beam exposure mask according to claim 1, wherein the electron beam exposure mask constitutes a membrane mask or a stencil mask.

8.-12. (Cancelled).